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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION N
10/024,958	12/18/2001	Melisa Buie	elisa Buie AMA/4213.P1/ETCH/METAL/JB 3439	
32588 75	590 07/06/2004	EXAMINER		INER
APPLIED MATERIALS, INC. 2881 SCOTT BLVD. M/S 2061 SANTA CLARA, CA 95050			CHEN, KIN CHAN	
			ART UNIT	PAPER NUMBER
			1765	
			DATE MAILED: 07/06/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

<b>,</b>	Application No.	Applicant(s)			
Advisory Action	10/024,958	BUIE ET AL.			
Advisory Action	Examiner	Art Unit			
	Kin-Chan Chen	1765			
The MAILING DATE of this communication appe	ears on the cover sheet with the c	correspondence address			
THE REPLY FILED 17 June 2004 FAILS TO PLACE THE Therefore, further action by the applicant is required to a final rejection under 37 CFR 1.113 may only be either: (1 condition for allowance; (2) a timely filed Notice of Appel Examination (RCE) in compliance with 37 CFR 1.114.	void abandonment of this application (i) a timely filed amendment whi	cation. A proper reply to a ch places the application in			
PERIOD FOR RE	PLY [check either a) or b)]				
a) The period for reply expiresmonths from the mailing of b) The period for reply expires on: (1) the mailing date of this Adverse, will the statutory period for reply expire later the ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS 706.07(f).  Extensions of time may be obtained under 37 CFR 1.136(a). The dath have been filed is the date for purposes of determining the period of extensions of the shortened (b) above, if checked. Any reply received by the Office later than three moderned patent term adjustment. See 37 CFR 1.704(b).	risory Action, or (2) the date set forth in the an SIX MONTHS from the mailing date of FILED WITHIN TWO MONTHS OF THE te on which the petition under 37 CFR 1.1 sion and the corresponding amount of the I statutory period for reply originally set in	the final rejection.  E FINAL REJECTION. See MPEP  36(a) and the appropriate extension fee fee. The appropriate extension fee under the final Office action; or (2) as set forth in			
<ul> <li>1. A Notice of Appeal was filed on Appellant's 37 CFR 1.192(a), or any extension thereof (37 CF</li> <li>2. The proposed amendment(s) will not be entered b</li> </ul>	R 1.191(d)), to avoid dismissal of				
		NOTELL			
(a) L they raise new issues that would require furth	`	see NOTE below);			
(b) ☐ they raise the issue of new matter (see Note to the last the results of the second to the sec	,				
(c) they are not deemed to place the application issues for appeal; and/or	in better form for appeal by mat	erially reducing or simplifying the			
(d)  they present additional claims without cancel NOTE:	ing a corresponding number of	finally rejected claims.			
3. Applicant's reply has overcome the following reject	tion(s):				
4. Newly proposed or amended claim(s) would canceling the non-allowable claim(s).	be allowable if submitted in a s	eparate, timely filed amendment			
5. ☐ The a) ☐ affidavit, b) ☐ exhibit, or c) ☐ request for application in condition for allowance because: se		sidered but does NOT place the			
6. The affidavit or exhibit will NOT be considered becaused by the Examiner in the final rejection.	cause it is not directed SOLELY	to issues which were newly			
For purposes of Appeal, the proposed amendment(s) a) will not be entered or b) will be entered and an explanation of how the new or amended claims would be rejected is provided below or appended.					
The status of the claim(s) is (or will be) as follows:					
Claim(s) allowed:					
Claim(s) objected to:					
Claim(s) rejected:					
Claim(s) withdrawn from consideration:					
8. The drawing correction filed on is a) app	roved or b) disapproved by	the Examiner.			
Note the attached Information Disclosure Statement(s)( PTO-1449) Paper No(s)					
10.☑ Other: <u>references cited for evidences</u>	,	Kin-Chan Chen Primary Examiner Art Unit: 1765			

U.S. Patent and Trademark Office PTOL-303 (Rev. 11-03)

Application/Control Number: 10/024,958

Art Unit: 1765

## Response to Request-for-reconsideration-after-final

1. In response to applicant's argument that there is no suggestion to combine the references, the examiner recognizes that obviousness can only be established by combining or modifying the teachings of the prior art to produce the claimed invention where there is some teaching, suggestion, or motivation to do so found either in the references themselves or in the knowledge generally available to one of ordinary skill in the art. See *In re Fine*, 837 F.2d 1071, 5 USPQ2d 1596 (Fed. Cir. 1988) and *In re Jones*, 958 F.2d 347, 21 USPQ2d 1941 (Fed. Cir. 1992). As has been stated in the office action, it would have been obvious to one with ordinary skilled in the art to modify Kornblit by using carbon monoxide as taught by Meyer because each of which is taught by the prior art to be useful for the same purpose of etching chromium coated glass substrate.

"It is prima facie obvious to use two compositions (two methods) each of which is taught by the prior art to be useful for the same purpose." In re Kerkhoven 205 USPQ 1069 (CCPA 1980). In re Susi 169 USPQ 423, 426 (CCPA 1971). See also Ex parte Quadranti 25 USPQ 2d 1071 (BPAI 1992).

2. Applicant has argued the compositions (ratios of the etching gases), processing parameters (such as power and pressure) and carrier gas (e.g., helium). As has been stated in the office action, they are commonly determined by routine experiment. The process of conducting routine optimizations so as to produce an expected result is obvious to one of ordinary skill in the art. It is noted that applicant did not traverse the aforementioned conventionality ,which have been stated in the previous office action (October 20, 2003). However, The examiner would like

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to further provide some evidences (see Demmin et al. US 6,635,185, beginning at col. 7, line 15) to show the compositions (ratios of the etching gases), processing parameters (such as power and pressure) are well-known result-effective variables in the art of dry etching, which can be optimized, also see MPEP 2144.05. As to carrier gas, as stated in the office action, Meyer teaches using carrier gas (col. 3, line 11) such as argon. Therefore, it includes helium because argon and helium are notoriously well-known carrier gases in the art of dry etching, also see the further evidences, Takada et al. (US 4,350,563; col. 7, line 57), Tachi (US 4,406,733; col. 2, line 57).

In light of comments above, the obviousness rejections are maintained.

July 1, 2004

DAN-CHAN CHEN PRIMARY EXAMINER